



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT

In re application of: PATRICK et al.

Attorney Docket No.:
LAM1P061/P0318

Application No.: 08/925,985

Examiner: MARKOFF, A.

Filed: September 9, 1997

Group: 1746

Title: APPARATUS FOR IMPROVING ETCH
UNIFORMITY AND METHODS
THEREFOR

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5-31-00

CERTIFICATE OF EXPRESS MAILING

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Signed: _____

Sue Funchess

PRELIMINARY AMENDMENT B

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Enclosed is a preliminary amendment in response to the Office Action dated March 1, 2000.

In the Claims:

Please cancel claim 3 and the original claims 11-24 and claims 34-35. Please amend claims 1 and 25-35, as follows:

1. (Twice Amended) In a plasma processing chamber, a method for improving etch uniformity while etching a semiconductor substrate, comprising:

placing said semiconductor substrate into a sacrificial substrate holder, said sacrificial substrate holder being configured to present a sacrificial etch portion surrounding said semiconductor substrate to a plasma within said plasma processing chamber to permit said plasma to etch a first surface of said semiconductor substrate and a first surface of said